

The inventions from which an election must be made include those listed in Groups I - IV:

- I. Claims 1 - 29, drawn to a method of reducing risk of detachment of a photoresist during development of the photoresist using a fluid developer, classified in class 430, subclass 434.
- II. Claims 30 - 38, drawn to a method of reducing photoresist poisoning by using a plasma treatment, classified in class 438, subclass 513.
- III. Claim 39, drawn to a method of reducing photoresist poisoning by using PECVD deposition of a capping film of alpha silicon, classified in class 438, subclass 563.
- IV. Claim 40, drawn to a method of reducing photoresist poisoning by using PECVD deposition of a capping film of alpha carbon, classified in class 438, subclass 562.

While applicants disagree with the determination that the Group III and Group IV inventions should be restricted as distinct inventions, this issue will not be addressed in detail at this time, as applicants want to elect the Group II invention, Claims 30 - 38, for prosecution in the present application. The Group II claims are distinct from the claims in the other Groups, and there is no traverse with respect to the restriction of these claims from the other claims which are pending in the application.

Applicants hereby elect to prosecute Claims 30 - 38, drawn to a method of reducing photoresist poisoning by plasma treating of the substrate on which the photoresist is to be deposited prior to deposition of the photoresist.

The Examiner is invited to contact applicants' attorney with any questions or suggestions, at the telephone number provided below.

Respectfully submitted,

A handwritten signature in cursive script, reading "Shirley L. Church", is written over a horizontal line.

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